

DUAL SEMINARS AT [TC]² THE CRUCIAL ELEMENTS OF FIT AND DESIGN

Ultimately, the fit and appearance of a garment depends on the successful execution of the pattern design and grading processes. The last seminars of 2005 on pattern development and grading will be offered in August and September.

INSTRUCTOR:

Elizabeth White has a unique background in both the technical execution of pattern development and textile design. Elizabeth covers the crucial nuances entailed in the skillful art of pattern development and grading.

PATTERN DEVELOPMENT SEMINAR: AUGUST 9-11, 2005

This seminar is designed to provide essential information to the aspiring pattern maker and others involved in the development and merchandising of a garment.

GRADING FOR FIT SEMINAR: SEPTEMBER 20-22, 2005

In this seminar, the basic principles of fit and grading the sample size pattern to the full range of sizes are detailed. Attendees should understand patternmaking, general grading principles, and basic CAD functions.



Attend both seminars and receive a 15% Discount off 'Grading for Fit.'

For this [TC]² Technology Communicator Special:

- Participant must **Register** for both seminars and **Attend** the Aug. 9th 'Pattern Development'
- Tuition is nonrefundable after Friday, July 15th

For more details about the seminars and other workshops scheduled for the remainder of 2005, go to <http://www.tc2.com/what/seminars.html>.

A RECENT SEMINAR PARTICIPANT COMMENTS:

"The best part of attending the program was getting the manufacturer's perspective of grading. As a tech designer, I needed to open up to my manufacturing partners."

Donna Lilley
Sears, Roebuck & Co.